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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KOZAWA et al.

Attorney Docket No: 100021-00065

Application No. 10/005,347

Art Unit: 1712

Filed: December 7, 2001

Examiner: K. Peng

For: SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,  
RESIST COPOSITION EMPLOYING IT, PATTERN-FORMING METHOD AND  
ELECTRONIC DEVICE FABRICATION METHOD

**AMENDMENT AFTER ALLOWANCE 37 CFR § 1.312**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

September 21, 2004

Sir:

Prior to issuance of the above-identified application, please amend the  
application as follows: